Plasma Etching Graduate Internship at Micron

Internship Description:

As an Intern in the Dry (plasma) Etch Research and Development Group in Boise, ID, you will design and optimize plasma etch processes for Micron's leading edge memory products. Primary areas of responsibility include plasma dry etch process characterization, optimization, design, troubleshooting, process transfer and fundamental research. Dry Etch Process Development Interns interact with groups such as process integration, electrical failure analysis, yield enhancement, manufacturing, and equipment vendors to ensure robust etch processes that meet the precise physical and electrical requirements for Micron products. All applicants in the midst of graduate level education with a research focus in plasma science and engineering will be considered.

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